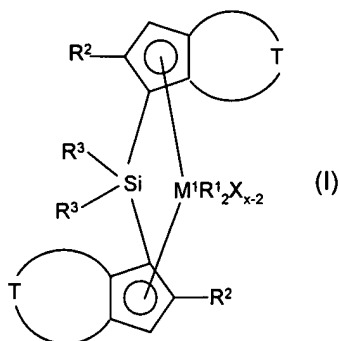
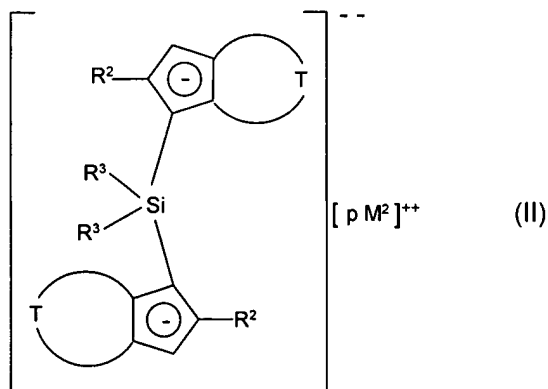


AMENDMENTS TO THE CLAIMS

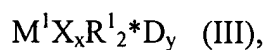
1. (currently amended) A process for the racemoselective preparation of silicon-bridged dialkyl-ansa-metallocenes of the formula (I)



which comprises reacting a ligand starting compound of the formula (II)



with a transition metal dialkyl compound of the formula (III)



where

M^1 is an element of group 4, 5 or 6 of the Periodic Table of the Elements[.];

R^1 are identical C_1 - C_{20} -alkyl or C_7 - C_{40} -arylalkyl radicals[.];

X are identical or different halogens[.];

- R^2 are identical or different C_1 - C_{40} radicals[[],];
- R^3 are identical or different C_1 - C_{40} radicals[[],];
- T is a divalent C_1 - C_{40} group which together with the cyclopentadienyl ring forms a further saturated or unsaturated ring system which has a ring size of from 5 to 12 atoms, where T may contain the heteroatoms Si, Ge, N, P, O or S in the ring system fused onto the cyclopentadienyl ring[[],];
- M^2 is Li, Na, K, MgCl, MgBr, MgI, Mg or Ca[[],];
- D is an uncharged Lewis base ligand[[],];
- x is equal to the oxidation number of M^1 minus 2[[],];
- y is from 0 to 2;
- and
- p is 1 in the case of doubly positively charged metal ions or 2 in the case of singly positively charged metal ions or metal ion fragments.

2. (currently amended) ~~A~~The process as claimed in claim 1, wherein

T is a 1,3-butadiene-1,4-diyl group which may be unsubstituted or be substituted by from 1 to 4 radicals R^4 , where the two 1,3-butadiene-1,4-diyl groups may be different[[],];

R^4 are identical or different C_1 - C_{20} radicals[[],];

M^1 is titanium, zirconium or hafnium[[],];

R^1 are identical C_1 - C_5 -alkyl or C_7 - C_{20} -arylalkyl radicals[[],]; and

X is halogen ~~and~~

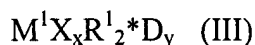
~~R^2 , R^3 , M^2 , D, p, x and y are as defined in claim 1.~~

3. (currently amended) ~~A~~The process as claimed in claim 1-~~or~~2, wherein the transition metal dialkyl compound of the formula (III) is produced at above -30°C by combining a compound M^1X_{x+2} with from 2 to 2.5 equivalents of a compound R^1M^3 in the presence of a ligand compound D, where

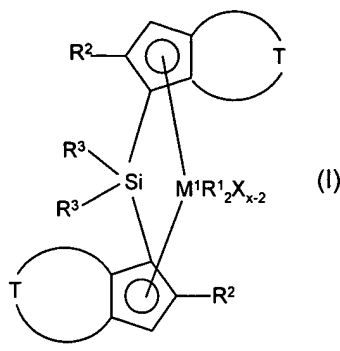
M^3 is Li^+ , Na^+ , K^+ , MgCl^+ , MgBr^+ , MgI^+ , $\frac{1}{2} [\text{Mg}^{++}]$ or $\frac{1}{2} [\text{Zn}^{++}]$, ~~and~~

~~the other variables are as defined in claim 1 or 2.~~

4. (currently amended) ~~A~~The process as claimed in claim 1-~~or~~2, wherein the ligand starting compound of the formula (II) ~~or~~ (V) is combined with the transition metal dialkyl compound of the formula (III) at above -30°C .
5. (currently amended) ~~A~~The process as claimed in claim 4, wherein ~~the~~a reaction mixture is maintained at from 30°C to 150°C for a period of at least 10 minutes after the reaction components have been combined.
6. (currently amended) ~~A~~The process as claimed in ~~any of claims~~claim 1 to 5, wherein the reaction is carried out in an organic solvent or solvent mixture which comprises at least 10% by volume of an ether.
7. (currently amended) ~~A~~The process as claimed in ~~any of claims~~claim 1 to 6, wherein ~~the~~a racemoselectivity = (proportion of rac – proportion of meso)/(proportion of rac + proportion of meso) is greater than zero.
8. (currently amended) ~~The use of~~A process comprising utilizing a transition metal dialkyl compound of the formula (III):



for the racemoselective preparation of silicon-bridged dialkyl-ansa-metallocenes of the formula (I):



wherein

M¹ is an element of group 4, 5 or 6 of the Periodic Table of the Elements;

R¹ are identical C₁-C₂₀-alkyl or C₇-C₄₀-arylalkyl radicals;

X are identical or different halogens;

R² are identical or different C₁-C₄₀ radicals;

R³ are identical or different C₁-C₄₀ radicals;

D is an uncharged Lewis base ligand;

y is from 0 to 2;

T is a divalent C₁-C₄₀ group which together with the cyclopentadienyl ring forms a further saturated or unsaturated ring system which has a ring size of from 5 to 12 atoms, where T may contain the heteroatoms Si, Ge, N, P, O or S in the ring system fused onto the cyclopentadienyl ring; and

x is equal to the oxidation number of M¹ minus 2.

9. (new) The process as claimed in claim 2, wherein the transition metal dialkyl compound of the formula (III) is produced at above -30°C by combining a compound M¹X_{x+2} with from 2 to 2.5 equivalents of a compound R¹M³ in the presence of a ligand compound D, where

M³ is Li⁺, Na⁺, K⁺, MgCl⁺, MgBr⁺, MgI⁺, ½ [Mg⁺⁺] or ½ [Zn⁺⁺].

10. (new) The process as claimed in claim 2, wherein the ligand starting compound of the formula (II) is combined with the transition metal dialkyl compound of the formula (III) at above -30°C.
11. (new) The process as claimed in claim 10, wherein a reaction mixture is maintained at from 30°C to 150°C for a period of at least 10 minutes after the reaction components have been combined.